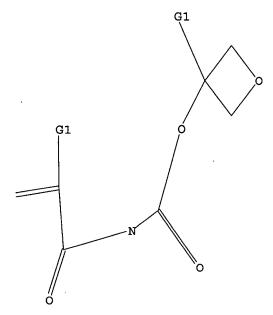
0 ANSWERS

L6 STRUCTURE UPLOADED

=> d 16 L6 HAS NO ANSWERS L6 STR



G1 Et,n-Pr,n-Bu,t-Bu

Structure attributes must be viewed using STN Express query preparation.

=> s 16 ful

FULL SEARCH INITIATED 11:15:34 FILE 'REGISTRY'
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100.0% PROCESSED

0 ITERATIONS

SEARCH TIME: 00.00.01

L7 0 SEA SSS FUL L6

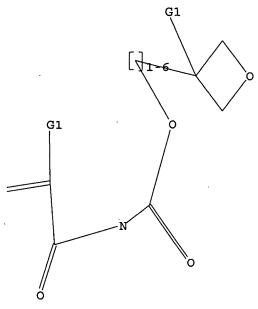
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L8 STRUCTURE UPLOADED

=> d 18

L8 HAS NO ANSWERS

L8 STR



G1 Et,n-Pr,n-Bu,t-Bu

Structure attributes must be viewed using STN Express query preparation.

=> s l8 ful FULL SEARCH INITIATED 11:17:25 FILE 'REGISTRY' FULL SCREEN SEARCH COMPLETED - 2 TO ITERATE

Uploading C:\Program Files\Stnexp\Queries\rkc072c.str

100.0% PROCESSED

2 ITERATIONS

0 ANSWERS

SEARCH TIME: 00.00.01

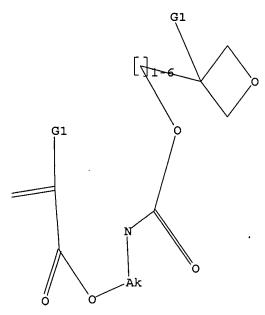
L9

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0 SEA SSS FUL L8

L10 STRUCTURE UPLOADED

=> d L10 HAS NO ANSWERS L10 STR



G1 Et,n-Pr,n-Bu,t-Bu

Structure attributes must be viewed using STN Express query preparation.

=> s l10 ful FULL SEARCH INITIATED 11:19:32 FILE 'REGISTRY' FULL SCREEN SEARCH COMPLETED - 16 TO ITERATE

100.0% PROCESSED

16 ITERATIONS

0 ANSWERS

SEARCH TIME: 00.00.01

L11

0 SEA SSS FUL L10

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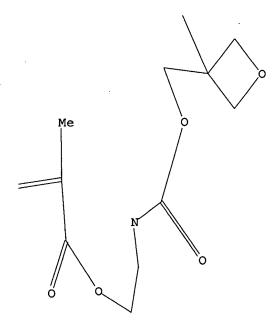
L12 STRUCTURE UPLOADED

=> d

L12 HAS NO ANSWERS

L12

STR



G1 Et,n-Pr,n-Bu,t-Bu

Structure attributes must be viewed using STN Express query preparation.

=> s k12 ful L13 19180 K12

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100.0% PROCESSED 6 ITERATIONS SEARCH TIME: 00.00.01

1 ANSWERS

SEARCH TIME: 00.00.01

L14 1 SEA SSS FUL L12

=> d

L14 ANSWER 1 OF 1 REGISTRY COPYRIGHT 2007 ACS on STN

RN 862453-34-7 REGISTRY

ED Entered STN: 02 Sep 2005

CN 2-Propenoic acid, 2-methyl-, 2-[[[(3-ethyl-3-oxetanyl)methoxy]carbonyl]ami
no]ethyl ester (9CI) (CA INDEX NAME)

MF C13 H21 N O5

SR CA

LC STN Files: CA, CAPLUS, USPATFULL

PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

- 1 REFERENCES IN FILE CA (1907 TO DATE)
- 1 REFERENCES IN FILE CAPLUS (1907 TO DATE)

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COST IN U.S. DOLLARS SINCE FILE TOTAL ENTRY SESSION FULL ESTIMATED COST 703.85 980.84

DISCOUNT AMOUNTS (FOR QUALIFYING ACCOUNTS) SINCE FILE TOTAL

CA SUBSCRIBER PRICE ENTRY SESSION 0.00 -67.86

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FILE COVERS 1907 - 27 Apr 2007 VOL 146 ISS 19 FILE LAST UPDATED: 26 Apr 2007 (20070426/ED)

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http://www.cas.org/infopolicy.html

=> s 114

L15 1 L14

=> d bib abs hitstr

L15 ANSWER 1 OF 1 CAPLUS COPYRIGHT 2007 ACS on STN

AN 2005:823679 CAPLUS

DN 143:212295

TI Preparation of polymerizable (meth)acryloyl group-containing oxetane monomers

IN Kamata, Hirotoshi; Morinaka, Katsutoshi; Uchida, Hiroshi

PA Showa Denko K.K., Japan

SO PCT Int. Appl., 21 pp. CODEN: PIXXD2

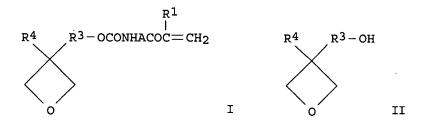
DT Patent

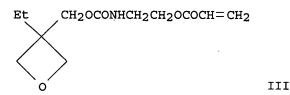
LA English

FAN. CNT 1

PATENT NO. KIND DATE APPLICATION NO. DATE

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              LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NA, NI, NO,
              NZ, OM, PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SY, TJ,
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                                                US 2006-588072
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PRAI JP 2004-32867
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     US 2004-545488P
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     WO 2005-JP2381
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os
     MARPAT 143:212295
GI
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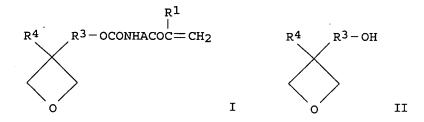
Polymerizable (meth) acryloyl group-containing oxetane [I; A = OR2, direct bond; R2 = divalent hydrocarbyl (which may contain an oxygen atom in the main chain); R1 = H, CH3; R3 = C1-6 (un) branched alkylene; R4 = C1-6 (un) branched alkyl] monomers are prepared in high yield and selectivity by the addition reaction of (meth) acrylate isocyanates H2C:C(R1)CO(A)NCO with 3-(hydroxyalkyl)-substituted oxetanes (II) in the presence of a tertiary amine or tin-compound catalyst. Thus, 2-acryloyloxyethyl isocyanate was mixed in Et acetate containing dibutyltin dilaurate and reacted with 3-ethyl-3-(hydroxymethyl) oxetane, producing an oxetanyl group-containing methacrylate ester monomer (III).

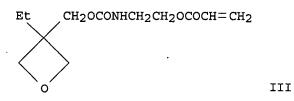
RN 862453-34-7 CAPLUS

CN 2-Propenoic acid, 2-methyl-, 2-[[[(3-ethyl-3-oxetanyl)methoxy]carbonyl]ami no]ethyl ester (9CI) (CA INDEX NAME)

=> d his

	BA, HR, IS	, YU			
	US 2007060760	A1	20070315	US 2006-588072	20060731
PRAI	JP 2004-32867	Α	20040210		
	US 2004-545488P	P	20040219		
	WO 2005-JP2381	W	20050209		
os	MARPAT 143:212295				
GI					





AB Polymerizable (meth)acryloyl group-containing oxetane [I; A = OR2, direct bond; R2 = divalent hydrocarbyl (which may contain an oxygen atom in the main chain); R1 = H, CH3; R3 = C1-6 (un)branched alkylene; R4 = C1-6 (un)branched alkyl] monomers are prepared in high yield and selectivity by the addition reaction of (meth)acrylate isocyanates H2C:C(R1)CO(A)NCO with 3-(hydroxyalkyl)-substituted oxetanes (II) in the presence of a tertiary amine or tin-compound catalyst. Thus, 2-acryloyloxyethyl isocyanate was mixed in Et acetate containing dibutyltin dilaurate and reacted with 3-ethyl-3-(hydroxymethyl)oxetane, producing an oxetanyl group-containing methacrylate ester monomer (III).

```
=> s oxetane
L1
        4682 OXETANE
=> s acryloyl
        11113 ACRYLOYL
=> s l1 and l2
L3
           28 L1 AND L2
=> d 1-28 bib abs
T.3
    ANSWER 1 OF 28 CAPLUS COPYRIGHT 2007 ACS on STN
AN
    2007:116310 CAPLUS
DN
    146:172007
TI
    Fabrication of optical members including index-different sections with
    variety of shape
IN
    Koho, Satoshi; Eriyama, Yuichi
PA
    Jsr Ltd., Japan
SO
    Jpn. Kokai Tokkyo Koho, 17pp.
    CODEN: JKXXAF
DT
    Patent
LA
    Japanese
FAN.CNT 1
    PATENT NO.
                       KIND
                              DATE
                                         APPLICATION NO.
                                                                DATE
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                              -----
                                          ______
PΤ
    JP 2007025091
                              20070201
                                       JP 2005-205132
                                                                20050714
PRAI JP 2005-205132
                               20050714
    The process involves these steps; applying compns. of (A) radical
    monomers, (B) radical initiators, (C) cationic polymerization monomers, and
    optionally (D) cationic photopolymn. initiators on supports, exposing the
     same to light in atmospheric containing ≥1 volume% O, and heating or exposing
     the same to light with different wavelength from that of the former, to
     form polymers of C around and/or upon the preformed polymers of A. The C
    polymers have smaller n than that of A polymers. Waveguides or microlens
    arrays can be manufactured as above without development stage.
L3
    ANSWER 2 OF 28 CAPLUS COPYRIGHT 2007 ACS on STN
AN
    2006:1031534 CAPLUS
DN
     145:357658
ΤI
    Thermally radical- and thermally cationic-curable vinyl polymer
    compositions with low viscosity and high mechanical strength
IN
    Tamai, Hitoshi; Nakagawa, Yoshiki
PA
    Kaneka Corp., Japan
    Jpn. Kokai Tokkyo Koho, 44pp.
SO
    CODEN: JKXXAF
DT
    Patent
LA
    Japanese
FAN.CNT 1
                              DATE
    PATENT NO.
                        KIND
                                         APPLICATION NO.
                                                                DATE
     ______
                       ____
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                                          ______
                                          JP 2005-89220
PΙ
    JP 2006265483
                        Α
                               20061005
                                                                20050325
PRAI JP 2005-89220
                               20050325
    The compns., useful for seals and gaskets, comprise vinyl polymers having
    ≥2 O2CCRa:CH2 (I; Ra = H, C1-20 organic group) in a mol. containing
    ≥1 I at end groups and epoxides and/or oxetane compds.
    Thus, a composition comprising acryloyl-terminated Bu acrylate-Et
    acrylate-2-methoxyethyl acrylate copolymer manufactured by living atom transfer
```



radical polymerization (ATRP) in the presence of CuBr 70, benzoperoxide (Nyper

BW) 0.7, 3,4-epoxycylohexylmethyl 3,4-epoxycylohexanecarboxylate (Celloxide 2021P) 30, thermally cationic polymerization catalyst of (2-butenyl)tetramethylenesulfonium hexafluoroantimonate (Adeka Opton CP 77) 0.45 part was hot-pressed into a sheet showing 30% modulus (JIS K 6301) 0.22 MPa, strength at break 1.42 MPa, and elongation at break 115%.

- L3 ANSWER 3 OF 28 CAPLUS COPYRIGHT 2007 ACS on STN
- AN 2006:489898 CAPLUS
- DN 145:9782
- TI Coating compositions with good scratch, acid, and solvent resistance for automobile bodies
- IN Maeda, Shinichi; Saito, Yoshikazu; Toyama, Masayuki; Hayama, Yasushi
- PA Mitsubishi Rayon Co., Ltd., Japan
- SO Jpn. Kokai Tokkyo Koho, 28 pp.
- CODEN: JKXXAF
- DT Patent
- LA Japanese
- FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE	
ΡI	JP 2006131670	Α	20060525	JP 2004-319366	20041102	
PRAI	JP 2004-319366		20041102			

AB Title coating compns. comprise (A) a compound having a (meth) acryloyl group and an anhydride group formed by at least two carboxylic acid groups or one ester group and a carboxylic acid group, an acrylic copolymer having at least an epoxy group or an oxetane group, and a radical polymerization initiator. Thus, styrene 20, tridecyl methacrylate 15, glycidyl methacrylate 45, and 4-hydroxybutyl acrylate were polymerized to give a copolymer with epoxy equivalent 315 g/equiv and weight average

mol. weight 5000, 315 parts of which was mixed with 2-acryloyloxy trimellitic anhydride obtained from 2-hydroxyethyl acrylate and trimellitic anhydride 283, 1-hydroxycyclohexylphenylketone 18, Sanol LS 765 12, tetraethylphosphonium bromide 6, and Modaflow 1.2 parts, applied on a coated steel plate, dried at 160° for 30 min, and irradiated with a UV ray to give a test piece, showing good acid, solvent, and scratch resistance, and gloss retention, and pencil hardness F.

- L3 ANSWER 4 OF 28 CAPLUS COPYRIGHT 2007 ACS on STN
- AN 2006:199643 CAPLUS
- DN 145:505777
- TI Development of high performance photo-curable polymers and oligomers using novel reactions of oxetane compounds
- AU Nishikubo, Tadatomi; Kameyama, Atsushi
- CS Department of Applied Chemistry, Faculty of Engineering, Japan
- SO RadTech Europe 05: UV/EB--Join the Winning Technology, [Conference Proceedings], Barcelona, Spain, Oct. 18-20, 2005 (2005), Volume 2, 43-47 Publisher: RadTech Europe Association, The Hague, Neth. CODEN: 69HVYN
- DT Conference; General Review
- LA English
- AB A review. The authors recently found many new addition reactions of oxetanes with certain reagents such as phenols and carboxylic acids using certain quaternary onium salts or crown ether complexes as catalysts. More recently, we also found new anionic ring-opening polymerization of oxetanes containing pendant hydroxyl groups and alternating anionic ring-opening copolymn. of oxetanes with cyclic carboxylic anhydrides using appropriate catalyst system. These reactions have been widely applied to the synthesis of polymers and thermo-setting reactions of oxetane

resins. In this paper, we would like to introduce the application of these new reactions for the synthesis of high performance photo-curable polymers and oligomers containing pendant or terminal (meth)acryloyl groups. The authors also report the photochem. property of the resulting polymers and oligomers. Furthermore, the authors would like to talk about the synthesis of certain calixarenes and poly(imide)s containing oxetane groups as high performance materials and their photochem. reaction.

RE.CNT 15 THERE ARE 15 CITED REFERENCES AVAILABLE FOR THIS RECORD ALL CITATIONS AVAILABLE IN THE RE FORMAT

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L3 ANSWER 5 OF 28 CAPLUS COPYRIGHT 2007 ACS on STN
```

AN 2005:1075860 CAPLUS

DN 143:368070

TI Photoradically/photocationically curable compositions with low viscosity

IN Okada, Kenji; Nakagawa, Yoshiki

PA Kaneka Corporation, Japan

SO PCT Int. Appl., 65 pp.

CODEN: PIXXD2

DT Patent

LA Japanese

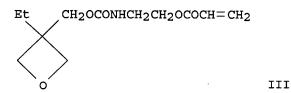
FAN.CNT 1

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																		ZM,	ZW
		RW:						MW,											
								RU,											
								GR,											
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	CA	2561		-				2005	1006		CA 2	005-3	2561	169		20	10501	325	
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								CZ,											
								MC,									110,	ıı,	
	CN	19383						2007) N E N :	225	
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- 11		I I I C														γ _			

polymers (>1 acryloyl group is a terminal group), (B) epoxy compds. and.or oxetane compds., (C) photoradical initiators, and (D) photocationic initiators. Thus, Bu acrylate, Et acrylate, and 2-methoxyethyl acrylate were polymerized in the presence of copper (I) bromide, pentamethyldiethylenetriamine, and di-Et 2,5-dibromoadipate, potassium acrylate was added therein and reacted to give acryloyl-terminated copolymer with number average mol. weight 16,900 and polydispersity 1.14, 100 parts of which was mixed with 2,2-diethoxyacetophenone 0.2, Epolite 4000 30, Adeka Optomer SP 172 1.5, and Irganox 1010 1 parts to give a composition with viscosity 150 Pa-s at 23°, which was cured by irradiation to give a cured product, showing 30% modulus 0.52 MPa, tensile strength at break 0.94 MPa, and elongation at break 52%.

RE.CNT 9 THERE ARE 9 CITED REFERENCES AVAILABLE FOR THIS RECORD ALL CITATIONS AVAILABLE IN THE RE FORMAT

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L3
     ANSWER 6 OF 28 CAPLUS COPYRIGHT 2007 ACS on STN
AN
     2005:823679 CAPLUS
DN
     143:212295
TI
     Preparation of polymerizable (meth)acryloyl group-containing
     oxetane monomers
IN
     Kamata, Hirotoshi; Morinaka, Katsutoshi; Uchida, Hiroshi
PA
     Showa Denko K.K., Japan
SO
     PCT Int. Appl., 21 pp.
     CODEN: PIXXD2
DT
     Patent
LA
     English -
FAN.CNT 1
     PATENT NO.
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                                 20050818
ΡI
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             GE, GH, GM, HR, HU, ID, IL, IN, IS, KE, KG, KP, KR, KZ, LC, LK,
             LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NA, NI, NO,
             NZ, OM, PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SY, TJ,
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                                 20070315
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     WO 2005-JP2381
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                                 20050209
os
     MARPAT 143:212295
GI
                  R^{1}
R4
      R^3 – OCONHACOC = CH_2
                                 R4
                                       R^3 - OH
                          Ι
                                              II
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AB Polymerizable (meth) acryloyl group-containing oxetane [I; A = OR2, direct bond; R2 = divalent hydrocarbyl (which may contain an oxygen atom in the main chain); R1 = H, CH3; R3 = C1-6 (un)branched alkylene; R4 = C1-6 (un)branched alkyl) monomers are prepared in high yield and selectivity by the addition reaction of (meth) acrylate isocyanates H2C:C(R1)CO(A)NCO with 3-(hydroxyalkyl)-substituted oxetanes (II) in the presence of a tertiary amine or tin-compound catalyst. Thus, 2-acryloyloxyethyl isocyanate was mixed in Et acetate containing dibutyltin dilaurate and reacted with 3-ethyl-3-(hydroxymethyl)oxetane, producing an oxetanyl group-containing methacrylate ester monomer (III).

L3 ANSWER 7 OF 28 CAPLUS COPYRIGHT 2007 ACS on STN .

AN 2005:428262 CAPLUS

DN 142:482780

TI Electrically conductive polymers containing condensed indoline rings and their manufacture

IN Kodera, Tatsuya

PA Mitsubishi Paper Mills, Ltd., Japan

SO Jpn. Kokai Tokkyo Koho, 28 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

1711.001 1								
PATENT NO.	KIND	DATE	APPLICATION NO.	DATE				
PI JP 2005126493	A	20050519	JP 2003-361092	20031021				
PRAI JP 2003-361092		20031021						
GI								

$$CH = CH - Ar^{2 \cdot 0} - C - C = CH_{2}$$
 R^{12}
 $CH = CH - Ar^{2 \cdot 0} - C - C = CH_{2}$
 R^{11}
 R^{10}

I

The manufacturing method of polymers, useful for electrophotog. photoreceptors, electroluminescent devices, etc., includes polymerizing I (R10 = alkyl, aryl, heterocyclic; R11 = H, amino, alkyl, alkoxy; R12 = H, alkyl; Ar2 = divalent group; Z3 = group forming saturated C5-8 ring). Manufacturing method including polymerizing mixts. of I and XCH2(OCH2CH2)mO2CC:CH2R2 (II; X= 3-R1-3-oxetanyl; R1,2 = H, alkyl; m = 0-2) are also claimed. Thus, I (R10 = Ph, R11 = H, R12 = Me, Ar2 = phenylene, Z3 = cyclopentane) and II (X= 3-R1-3-oxetanyl; R1 = Et, R2 = Me, m = 0) were polymerized in the presence of AIBN to give a copolymer with Mn 63,000 and Mw 92,000. A multilayer photoreceptor containing charge-transporting layer comprising the copolymer showed electrostatic potential -600 V at applied voltage -6 kV and light exposure for decreasing the potential in half (E1/2) 1.0 lx-s.

```
L3
     ANSWER 8 OF 28 CAPLUS COPYRIGHT 2007 ACS on STN
AN
     2005:155387 CAPLUS
     142:246263
DN
    Dental adhesive composition
TI
IN
    Anzai, Misaki; Kawaguchi, Motoki
PA
    Dentsply-Sankin K. K., Japan
SO
    Eur. Pat. Appl., 13 pp.
     CODEN: EPXXDW
DT
     Patent
    English
LA
FAN.CNT 1
     PATENT NO.
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                               DATE
                                         APPLICATION NO.
                                                                 DATE
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                               20050223 EP 2004-19518
PΤ
    EP 1508321
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                                                                 20040817
        R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT,
            IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, PL, SK, HR
     JP 2005065902
                               20050317 JP 2003-298363
                       Α
                                                                 20030822
     US 2005054749
                         A1
                               20050310
                                          US 2004-920358
                                                                 20040818
PRAI JP 2003-298363
                        Α
                               20030822
    A dental adhesive composition which can quickly be hardened even in the
     presence of oxygen without using a radical generating agent such as a
    peroxide or a photopolymn. initiator, to give high bond strength,
     comprises a carboxylic acid having a (meth)acryloyl group and a
     carboxyl group, both of which are attached to an aromatic ring; a bisphenol A
     derivative having 2 (meth)acryloyl groups; a hydroxylalkyl
     (meth)acrylate; a (meth)acrylate derivative having an acid group; and at least
     one polymerization initiator selected from the group consisting of aromatic
     aliphatic amines, and aromatic sulfinic acids, the composition being
substantially
     free from any radical polymerization initiator. Thus, a composition was
obtained from
     different methacryloyl monomers.
             THERE ARE 10 CITED REFERENCES AVAILABLE FOR THIS RECORD
RE.CNT 10
             ALL CITATIONS AVAILABLE IN THE RE FORMAT
L3
    ANSWER 9 OF 28 CAPLUS COPYRIGHT 2007 ACS on STN
AN
     2005:13763 CAPLUS
DN
     142:103247
ΤI
    High-sensitivity shrink-proof holographic recording materials containing
     epoxides, their manufacture, and their recording
IN
    Sasa, Nobumasa
DΔ
    Konica Minolta Medical & Graphic, Inc., Japan
    Jpn. Kokai Tokkyo Koho, 20 pp.
SO
     CODEN: JKXXAF
DT
    Patent
LA
    Japanese
FAN.CNT 1
                                      APPLICATION NO.
    PATENT NO.
                        KIND
                               DATE
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                               -----
                                           -----
ΡI
    JP 2005003958
                        Α
                               20050106
                                           JP 2003-167597
                                                                 20030612
PRAI JP 2003-167597
                               20030612
os
    MARPAT 142:103247
AB
    The holog. recording materials contain (A) epoxides containing ≥1
    substituted oxirane rings on \alpha and/or \beta sites of oxirane rings,
    epoxidized fatty acid esters, epoxidized fatty acid glycerides, (B)
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photopolymn. initiators, and optionally, (C) oxetane ring-containing compds. and/or vinyl ethers, (D) (meth)acryloyl group-containing

compds. and photoradical polymerization initiators. The holog. recording materials form matrixes by ≥1 polymerization reaction selected from cationic epoxy polymerization, cationic vinyl ether polymerization, cationic alkenyl

ether polymerization, cationic arene ether polymerization, cationic ketene acetal

polymerization, epoxy-amine step polymerization, epoxy-mercaptan step polymerization, unsatd.

ester-amine step polymerization, unsatd. ester-mercaptan step polymerization, vinyl-silicone hydride step polymerization, isocyanate-hydroxyl step polymerization, and

isocyanate-amine step polymerization. In another alternative, the holog. recording materials form matrixes by curing of inorg. or organic matrix precursors which may comprise RnM(OR')4-n (M = ≥ 3 -valent metal element, preferably, Si, Ti, Ge, Zr, V, Al; R = alkyl, allyl; R' = $C\leq 4$ lower alkyl; n = 1, 2). The holog. recording materials are are manufactured by mixing matrix-forming substances, their curing to give matrixes, and irradiation with actinic light for holog. recording.

- L3 ANSWER 10 OF 28 CAPLUS COPYRIGHT 2007 ACS on STN
- AN 2004:1014409 CAPLUS
- DN 142:7357
- TI Active energy curable resin compositions with good curability and low reflectance angle for optical disks
- IN Makino, Shinji
- PA Mitsubishi Rayon Co., Ltd., Japan
- SO Jpn. Kokai Tokkyo Koho, 17 pp. CODEN: JKXXAF
- DT Patent
- LA Japanese

FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI JP 2004331872	Α	20041125	JP 2003-131585	20030509
PRAI JP 2003-131585		20030509		

Title compns. comprise (A) compds. having ≥2 oxetane rings, (B) compds. having ≥2 oxirane rings, (C) cationic photoinitiators, (D) compds. having ≥1 (meth) acryloyl group, and (E) radical photoinitiators. Thus, a composition comprising OXT 121 25, YD 8125 bisphenol A diglycidyl ether 25, UVI 6990 photoinitiator 3.0, U 2PHA diacrylate 5.0, and Irgacure 184 1.0 parts was applied on a silver-coated Panlite AD 9000TG optical disk and irradiated with a high pressure mercury lamp to give a test piece with reflectance angle 0.16° initially and 0.06° after durability test, transmittance 91% at 400 nm, 93% at 500 nm, and 93% at 700 nm, good surface hardness and reliability.

- L3 ANSWER 11 OF 28 CAPLUS COPYRIGHT 2007 ACS on STN
- AN 2004:996235 CAPLUS
- DN 141:429659
- TI Photocuring/thermosetting ink-jet composition and printed wiring board using same
- IN Kakinuma, Masahisa; Kusama, Masatoshi; Ushiki, Shigeru
- PA Taiyo Ink Manufacturing Co., Ltd., Japan
- SO PCT Int. Appl., 21 pp. CODEN: PIXXD2
- DT Patent
- LA Japanese
- FAN.CNT 1

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PATENT NO.
                            KIND
                                    DATE
                                                 APPLICATION NO.
                                                                           DATE
                                                 ______
                                                                           ------
                                               WO 2004-JP6029
PI
     WO 2004099272
                            A1
                                    20041118
                                                                           20040507
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              CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, EG, ES, FI, GB, GD,
              GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NA, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SY,
              TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW
          RW: BW, GH, GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW, AM,
              AZ, BY, KG, KZ, MD, RU, TJ, TM, AT, BE, BG, CH, CY, CZ, DE, DK,
              EE, ES, FI, FR, GB, GR, HU, IE, IT, LU, MC, NL, PL, PT, RO, SE,
              SI, SK, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE,
              SN, TD, TG
     EP 1624001
                                                EP 2004-731714
                             A1
                                    20060208
              AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT,
              IE, SI, FI, RO, CY, TR, BG, CZ, EE, HU, PL, SK
     CN 1784432
                             Α
                                    20060607
                                                 CN 2004-80012609
                                                                           20040507
     US 2006058412
                             A1
                                    20060316
                                                 US 2005-269836
                                                                           20051109
PRAI JP 2003-131742
                             Α
                                    20030509
     WO 2004-JP6029
                             W
                                    20040507
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AB A photocuring/thermosetting ink-jet composition contains (A) a monomer having a (meth)acryloyl group and a thermosetting functional group in the mol., (B) a photoreactive diluent other than the component (A) having a weight-average mol. weight of not more than 700, and (C) a photopolymn. initiator,

and has a viscosity of not more than 150 mPa·s at 25°. A solder resist pattern is directly drawn on a printed wiring board by an ink-jet printer using the above-mentioned composition, and the pattern is primarily cured by irradiation with an active energy beam and then further cured by heat.

RE.CNT 15 THERE ARE 15 CITED REFERENCES AVAILABLE FOR THIS RECORD ALL CITATIONS AVAILABLE IN THE RE FORMAT

- L3 ANSWER 12 OF 28 CAPLUS COPYRIGHT 2007 ACS on STN
- AN 2003:1000504 CAPLUS
- DN 141:242819
- TI Product class 4: organometallic complexes of copper
- AU Heaney, H.; Christie, S.
- CS Dept. of Chemistry, University of Loughborough, Loughborough, LE11 3TU, UK
- SO Science of Synthesis (2004), 3, 305-662 CODEN: SSCYJ9
- PB Georg Thieme Verlag
- DT Journal; General Review
- LA English
- AB A review. The use of copper and related complexes in applications to organic synthesis is reviewed.
- RE.CNT 1706 THERE ARE 1706 CITED REFERENCES AVAILABLE FOR THIS RECORD ALL CITATIONS AVAILABLE IN THE RE FORMAT
- L3 ANSWER 13 OF 28 CAPLUS COPYRIGHT 2007 ACS on STN
- AN 2003:929612 CAPLUS
- DN 139:397036
- TI Oxetane-base polyol (meth)acrylates, their curable compositions, and hard coatings containing them with good heat and water resistance
- IN Sauchi, Yasuyuki; Sasaki, Hiroshi
- PA Toa Gosei Chemical Industry Co., Ltd., Japan
- SO Jpn. Kokai Tokkyo Koho, 13 pp. CODEN: JKXXAF

DT Patent LA Japanese

FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI JP 2003335854 PRAI JP 2002-143719 GI	A	20031128 20020517	JP 2002-143719	20020517

AB The invention relates to the (meth)acrylates having ≥2 (meth) acryloyl groups manufactured by heat-cationic-polymerizing I (R1 = H, alkyl, aryl, arylalkyl) to obtain polyols and esterifying them with (meth)acrylic acid. Thus, a composition comprising 3-ethyl-3-(hydroxymethyl)oxetane homopolymer acrylate was applied on a substrate and UV-cured to give a coating showing pencil hardness 4H, storage modulus 1.08 + 109 at 210°, and water absorption 1.32%.

- L3 ANSWER 14 OF 28 CAPLUS COPYRIGHT 2007 ACS on STN
- AN 2003:368907 CAPLUS
- DN 138:369365
- TI Oxetane-containing (meth) acrylate esters, their manufacture, and their use as dental monomers and monomers for grafting polyolefins
- IN Miyazaki, Kazuhisa; Ota, Seiji; Akie, Hideyuki
- PA Mitsui Chemicals Inc., Japan
- SO Jpn. Kokai Tokkyo Koho, 6 pp.

CODEN: JKXXAF

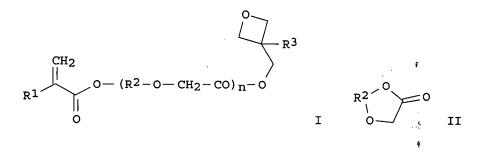
DT Patent

LA Japanese

FAN.CNT 1

GI

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI JP 2003137878	Α	20030514	JP 2001-332394	20011030
PRAI JP 2001-332394		20011030		,
OS MARPAT 138:369365				



AB Title esters I [R1 = H, Me; R2 = (ether bond-containing) linear or branched alkylene; R3 = linear alkyl; n = 1-4], useful for coatings and adhesives

as well, are manufactured by ring-cleavage esterification of lactones II (R2 = same as above) with 3-alkyl-3-hydroxymethyloxetane in the presence of base catalysts, followed by esterification of the resulting products with (meth)acryloyl halide. Thus, 1,4-dioxan-2-one was reacted with 3-ethyl-3-hydroxymethyloxetane in the presence of K2CO3 to give 28% 3-ethyl-3-oxetanylmethyl 2-hydroxyethoxyacetate, which was esterified with acryloyl chloride to give 40% 3-ethyl-3-oxetanylmethyl 2-acryloxyethoxyacetate.

- L3 ANSWER 15 OF 28 CAPLUS COPYRIGHT 2007 ACS on STN
- AN 2003:366797 CAPLUS
- DN 138:369360
- TI Oxetane-containing (meth) acrylate esters, their manufacture, and their use as dental monomers and monomers for grafting polyolefins
- IN Miyazaki, Kazuhisa; Ota, Seiji
- PA Mitsui Chemicals Inc., Japan
- SO Jpn. Kokai Tokkyo Koho, 6 pp.
 - CODEN: JKXXAF
- DT Patent
- LA Japanese
- FAN.CNT 1

KIND	DATE	APPLICATION NO.	DATE
Α	20030514 20011029	JP 2001-330883	20011029
		A 20030514	A 20030514 JP 2001-330883

$$H_2C = C - CO \left\{ O - R^2 - CO \right\} O - CH_2 R^3$$

- Title esters I [R1 = H, Me; R2 = (ether bond-containing) linear or branched alkylene; R3 = linear alkyl; n = 1-4], useful for coatings and adhesives as well, are manufactured by transesterification between HO(R2CO2)nR4 (R2, R4, n = same as above) and 3-alkyl-3-hydroxymethyloxetane in the presence of catalysts, followed by esterification of the resulting products with (meth)acryloyl halide. Thus, Et lactate was reacted with 3-ethyl-3-hydroxymethyloxetane in the presence of Ti(OCHMe2)4 to give 80% 3-ethyl-3-oxetanylmethyl lactate, which was esterified with acryloyl chloride to give 89% 3-ethyl-3-oxetanylmethyl 2-acryloxypropanoate.
- L3 ANSWER 16 OF 28 CAPLUS COPYRIGHT 2007 ACS on STN
- AN 2003:352823 CAPLUS
- DN 139:85711
- TI Combining Covalent and Noncovalent Cross-Linking: A Novel Terpolymer for Two-Step Curing Applications
- AU El-Ghayoury, Abdelkrim; Hofmeier, Harald; de Ruiter, Barteld; Schubert, Ulrich S.
- CS Laboratory of Macromolecular Chemistry and Nanoscience, Eindhoven University of Technology and Dutch Polymer Institute, Eindhoven, 5600, Neth.

- SO Macromolecules (2003), 36(11), 3955-3959 CODEN: MAMOBX; ISSN: 0024-9297
- PB American Chemical Society
- DT Journal
- LA English
- AB A terpolymer of poly(Bu acrylate) bearing terpyridine as well as oxetane units was synthesized by free radical polymerization and characterized using NMR, UV-vis, and GPC. Subsequently, UV-vis expts. indicated clearly a noncovalent crosslinking of the terpyridine moieties by addition of iron(II) ions. Moreover, the ability of covalent crosslinking was studied by polymerizing the oxetane rings utilizing Lewis acids. IR spectroscopy and DSC expts. clearly revealed the success of the combination of both steps when utilizing iron(II) ions and AlCl3.
- RE.CNT 53 THERE ARE 53 CITED REFERENCES AVAILABLE FOR THIS RECORD ALL CITATIONS AVAILABLE IN THE RE FORMAT
- L3 ANSWER 17 OF 28 CAPLUS COPYRIGHT 2007 ACS on STN
- AN 2002:625102 CAPLUS
- DN 137:248043
- TI Atom transfer radical copolymerization (ATRCP) of a monomer bearing an oxetane group
- AU Singha, Nikhil K.; de Ruiter, Barteld; Schubert, Ulrich S.
- CS Lab. Macromolecular Organic Chem., Center Nanomaterials, Eindhoven Univ. Technology, Eindhoven, 5600 MB, Neth.
- SO Polymer Preprints (American Chemical Society, Division of Polymer Chemistry) (2002), 43(2), 165-166
 CODEN: ACPPAY; ISSN: 0032-3934
- PB American Chemical Society, Division of Polymer Chemistry
- DT Journal; (computer optical disk)
- LA English
- AB The atom transfer radical polymerization of Me methacrylate with 3-ethyl-3-(acryloyloxymethyl)oxetane is described. Anal. of the copolymer confirmed that the oxetane ring did not open during polymerization
- RE.CNT 14 THERE ARE 14 CITED REFERENCES AVAILABLE FOR THIS RECORD ALL CITATIONS AVAILABLE IN THE RE FORMAT
- L3 ANSWER 18 OF 28 CAPLUS COPYRIGHT 2007 ACS on STN
- AN 2001:663120 CAPLUS
- DN 136:6399
- TI Synthesis and photochemical reaction of high performance UV curing oligomers
- AU Nishikubo, Tadatomi; Kameyama, Atsushi
- CS Department of Applied Chemistry, Faculty of Engineering, Kanagawa University, Kanagawa-ku, Yokohama, 221-8686, Japan
- SO Polymer Preprints (American Chemical Society, Division of Polymer Chemistry) (2001), 42(2), 722-723
 CODEN: ACPPAY; ISSN: 0032-3934
- PB American Chemical Society, Division of Polymer Chemistry
- DT Journal; (computer optical disk)
- LA English
- AB Calixarene derivs. containing (meth)acrylate, vinyl ether, propargyl ether, oxetane, oxirane, or spiro ortho ester groups were synthesized by reaction of calixarenes with (meth)acrylic acid derivs., vinyl ether compds., propargyl bromide, oxetane derivs., epibromohydrin, and spiro ortho ester derivs. The calixarene derivs. containing photoreactive groups had excellent thermal stability and high photochem. reactivity. The calixarene derivs. are of interest for UV curing systems, e.g., inks, coatings, solder masks, adhesives, and microelectronics uses.

RE.CNT 11 THERE ARE 11 CITED REFERENCES AVAILABLE FOR THIS RECORD ALL CITATIONS AVAILABLE IN THE RE FORMAT

- L3 ANSWER 19 OF 28 CAPLUS COPYRIGHT 2007 ACS on STN
- AN 2001:143711 CAPLUS
- DN 134:194666
- TI Actinic ray-curable sulfur-containing compositions with good curability and manufacture of coatings
- IN Maruyama, Tsutomu
- PA Kansai Paint Co., Ltd., Japan
- SO Jpn. Kokai Tokkyo Koho, 7 pp. CODEN: JKXXAF
- DT Patent
- LA Japanese

FAN.CNT 1

PA	TENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI JP	2001055507	Α	20010227	JP 1999-232626	19990819
DDAT .TD	1999-232626		19990819		

AB The compns. contain (A) 5-100 parts S-containing compds. manufactured by a reaction

of compds. (average mol. weight 150-1000) having ≥2 SH and compds. having 1 acryloyl group and ≥2 alkoxysilyl groups and optional compds. having 1 acryloyl group and ≥1 epoxy groups and/or oxetane rings at acryloyl/SH molar ratio

0.5-1.2, (B) 0-95 parts photochem. cationically reactive compds., and (C) 0.05-20 parts photochem. cationic polymerization initiators. Thus, a

composition
containing 100 parts reaction product of pentaerythritol
tetrakis(mercaptoacetate) and 3-acryloxypropyl trimethoxysilane and 4
parts CI 2758 (sulfonium salt-based initiator) was applied on a glass

plate and cured by UV-irradiation to give a coating showing pencil hardness 6H.

- L3 ANSWER 20 OF 28 CAPLUS COPYRIGHT 2007 ACS on STN
- AN 1999:810952 CAPLUS
- DN 132:51248
- TI Photocurable hydrolyzed silane composition and photocured product
- IN Sekiguchi, Manabu; Sugiyama, Naoki; Sato, Hozumi
- PA Jsr Corp., Japan
- SO Eur. Pat. Appl., 38 pp.

CODEN: EPXXDW

- DT Patent
- LA English

FAN.CNT 1

PATE	ENT NO.	KIND	DATE	APPLICATION NO.	DATE
					
PI EP 9	965618	A1	19991222	EP 1999-111732	19990617
EP 9	965618	B1	20040102		
	R: AT, BE, CH,	DE, DK	, ES, FR,	GB, GR, IT, LI, LU, NL,	SE, MC, PT,
	IE, SI, LT,	LV, FI	, RO		
JP 2	2000001648	A	20000107	JP 1998-170885	19980618
JP 2	2000026730	Α	20000125	JP 1998-194817	19980709
TW 4	182817	В	20020411	TW 1999-88110061	19990616
KR 2	2000006232	Α	20000125	KR 1999-22643	19990617
US 6	5207728	B1	20010327	US 1999-335269	19990617
JP 2	2000109560	A	20000418	JP 1999-219938	19990803
JP 2	2000109694	Α	20000418	JP 1999-219939	19990803
JP 2	2000109695	Α	20000418	JP 1999-220750	19990804

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JP 1998-170885 A
JP 1998-194817 A
JP 1998-220512 A
JP 1998-220512
PRAI JP 1998-170885
                                19980618
                                19980709
                                19980804
                         Α
     JP 1998-220513
                                19980804
     JP 1998-220514
                         Α
                                19980804
AB
     Disclosed is a photo-curable composition comprising the following components
     (A) to (C): (A) hydrolyzable silane compound represented by the general
     formula (1) or a hydrolyzate thereof: (R1)pSi(X)4-p (1) wherein R1 is a
     non-hydrolyzable organic group having 1 to 12 carbon atoms, X is a
     hydrolyzable group, and p is an integer of 0 to 3; (B) photo acid
     generator; and (C) dehydrating agent. By such constitution, it is
     possible to provide a photo-curable composition which has a rapid photo-curable
     rate, is excellent in characteristics such as storage stability, heat
     resistance, weather-ability, scratch resistance and the like, and is
     applicable to base materials having low heat resistance such as plastics,
     as well as a cured product obtained therefrom.
RE.CNT 3
              THERE ARE 3 CITED REFERENCES AVAILABLE FOR THIS RECORD
              ALL CITATIONS AVAILABLE IN THE RE FORMAT
L3
     ANSWER 21 OF 28 CAPLUS COPYRIGHT 2007 ACS on STN
AN
     1998:653719 CAPLUS
DN
     129:276496
TI
     Hydrolyzable and polymerizable oxetanesilanes
IN
     Moszner, Norbert; Volkel, Thomas; Stein, Sabine; Rheinberger, Volker
PA
     IVOCLAR A.-G., Liechtenstein
     Eur. Pat. Appl., 21 pp.
SO
     CODEN: EPXXDW
DT
     Patent
LΑ
     German
FAN.CNT 1
                       KIND
                               DATE
                                          APPLICATION NO.
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                                           ______
                                                                  -----
PΤ
     EP 867443
                         A2
                                          EP 1998-250089
                                19980930
                                                                  19980313
     EP 867443
                         A3
                                20000628
     EP 867443
                         B1
                                20030806
        R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT,
             IE, SI, LT, LV, FI, RO
    DE 19714324
                         A1
                                19981029
                                           DE 1997-19714324
                                                                   19970325
    DE 19714324
                                20040902
                         B4
    AT 246691
                        Т
                                20030815
                                           AT 1998-250089
                                                                   19980313
                        A1
     CA 2232960
                                19980925
                                           CA 1998-2232960
                                                                   19980324
                        С
     CA 2232960
                                20020129
    JP 10330485
                        A
A
                                           JP 1998-77593
                                19981215
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    US 6034151
                                20000307
                                           US 1998-47592
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    US 6096903
                        Α
                                20000801
                                           US 1998-47659
                                                                  19980325
    US 6284898
                                           US 2000-591358
                         B1
                                20010904
PRAI DE 1997-19714324
                        Α
                                19970325
    US 1997-52563P
                         P
                                19970715
    US 1997-52605P
                         P
                                19970715
    US 1998-47659
                         A3
                               19980325
os
    MARPAT 129:276496
     The title compds., with specified structure, which can be polymerized at room
AB
     temperature with very little shrinkage, are prepared Stirring
     3-ethyl-3-(hydroxymethyl)oxetane with acryloyl
     chloride in Et20 containing collidine at room temperature for 6 h gave 50%
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acrylate
ester, reaction of which with 3-(trimethoxysilyl)-1-propanethiol at room
temperature for 48 h gave 81% (3-ethyl-3-oxetanyl)methyl 3-[[3(trimethoxysilyl)propyl]thio]propionate (I). Hydrolytic polymerization of an

equimolar mixture of I and Me2Si(OMe)2 in refluxing EtOH gave a condensate which was used in a dental cement.

L3

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ANSWER 22 OF 28 CAPLUS COPYRIGHT 2007 ACS on STN
AN
     1997:579788 CAPLUS
DN
     127:235757
TI
     Coating composition comprising a bicyclo- or spiro-orthoester-functional
     compound
IN
     Van Den Berg, Keimpe Jan; Hobel, Klaus; Klinkenberg, Huig; Noomen, Arie;
     Van Oorschot, Josephus Christiaan
PA
     Akzo Nobel N.V., Neth.
SO
     PCT Int. Appl., 69 pp.
     CODEN: PIXXD2
DT
     Patent
LA
     English
FAN.CNT 1
     PATENT NO.
                        KIND
                               DATE
                                           APPLICATION NO.
                                                                  DATE
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     WO 9731073
                                         WO 1997-EP892
ΡI
                               19970828
                         A1
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             LK, LR, LS, LT, LU, LV, MD, MG, MK, MN, MW, MX, NO, NZ, PL, PT,
             RO, RU, SD, SE, SG, SI, SK, TJ, TM, TR, TT, UA, UG, UZ, VN
         RW: KE, LS, MW, SD, SZ, UG, AT, BE, CH, DE, DK, ES, FI, FR, GB, GR,
             IE, IT, LU, MC, NL, PT, SE, BF, BJ, CF, CG, CI, CM, GA, GN, ML,
             MR, NE, SN, TD, TG
     NL 1002427
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                                                                19960223
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                         A1
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     AU 9720930
                         Α
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     ZA 9701542
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                                19980727
                                           ZA 1997-1542
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                                           EP 1997-906123
     EP 882106
                                19981209
                         A1
                                                                  19970221
     EP 882106
                         В1
                                20000809
            AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT,
             IE, FI
     CN 1214717
                         Α
                                19990421
                                           CN 1997-193266
                                                                  19970221
     CN 1128851
                         В
                                20031126
     BR 9707735
                         Α
                                19990727
                                           BR 1997-7735
                                                                  19970221
     EP 942051
                         A2
                                19990915
                                           EP 1999-201141
                                                                  19970221
         R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT,
             IE, FI
     JP 2000506908
                         Т
                               20000606
                                           JP 1997-529818
                                                                  19970221
     AT 195331
                         T
                               20000815
                                           AT 1997-906123
                                                                  19970221
     ES 2150758
                         Т3
                               20001201
                                           ES 1997-906123
                                                                  19970221
     PT 882106
                        T
                               20010131
                                           PT 1997-906123
                                                                  19970221
     US 6297329
                        B1
                               20011002
                                           US 1997-804485
                                                                  19970221
     RU 2180674
                        C2
                               20020320
                                           RU 1998-117558
                                                                  19970221
     IN 1997MA00954
                        Α
                               20061006
                                           IN 1997-MA954
                                                                  19970506
     TW 418241
                        В
                               20010111
                                           TW 1997-86111273
                                                                  19970806
     NO 9803859
                        Α
                               19981020
                                           NO 1998-3859
                                                                  19980821
     AU 754919
                        B2
                               20021128
                                           AU 2000-56513
                                                                  20000906
                         Т3
     GR 3034728
                               20010131
                                           GR 2000-402417
                                                                  20001030
     US 2002161135
                        A1
                               20021031
                                           US 2001-935308
                                                                  20010822
     US 6593479
                         B2
                               20030715
PRAI NL 1996-1002427
                        Α
                               19960223
                         P
     US 1996-15878P
                               19960422
     EP 1997-906123
                         А3
                               19970221
     US 1997-804485
                         Α3
                               19970221
     WO 1997-EP892
                         W
                               19970221
AB
     A coating composition comprises a first compound of ≥1 bicyclo- or
```

spiro-orthoester group and a second compound of ≥2 hydroxyl-reactive groups. The latent hydroxyl groups of the bicyclo- or spiro-orthoester groups have to be deblocked and reacted with the hydroxyl-reactive groups of the second compound to be cured. Bicyclo-orthoester compds. are made from the corresponding oxetane compound, as are polymers comprising ≥1 bicyclo- or spiro-orthoester group. Thus, Desmodur N 3390 was mixed with 1,4-diethyl-2,6,7-trioxabicyclo[2.2.2]octane in the presence of p-MeC6H4SO3H and Bu2Sn dilaurate in solvent and sprayed onto steel panels showing pot life >1 day and dry time 100 min.

L3 ANSWER 23 OF 28 CAPLUS COPYRIGHT 2007 ACS on STN

AN 1996:709842 CAPLUS

DN 125:331792

TI Activation energy-curable coating compositions containing oxetane compounds with improved curability, gloss, adhesion, hardness, and crack resistance

IN Niwa, Makoto; Oota, Hiroyuki

PA Toa Gosei Kk, Japan

SO Jpn. Kokai Tokkyo Koho, 11 pp. CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI JP 08239623	A	19960917	JP 1995-64801	19950228
PRAI JP 1995-64801		19950228		
GI				

AB The coating compns. comprise compds. having 1-4 oxetane rings, cationic photopolymn. initiators, and optionally epoxides, vinyl ethers, and (meth)acryloyl compds. Thus, 100 parts compds. having 2 oxetane rings I and 4 parts diphenyl[p- (phenylthio)phenyl]sulfonium hexafluoroantimonate were stirred to give a composition, which was applied to a plywood and exposed to UV to give test pieces with JIS A hardness 7, cross-cut adhesion 8-10, >90% in 60° gloss, pencil hardness 3H, and .apprx.0 crack after thermal crack test (80° for 2 h, -20° for 2 h, repeated 2 times).

L3 ANSWER 24 OF 28 CAPLUS COPYRIGHT 2007 ACS on STN

AN 1996:705278 CAPLUS

DN 125:331101

TI Actinic beam-curable adhesive compositions of oxetane compounds

IN Niwa, Makoto; Oota, Hiroyuki

PA Toa Gosei Kk, Japan

SO Jpn. Kokai Tokkyo Koho, 12 pp. CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 08231938	Α	19960910	JP 1995-61898	19950224
PRAI	JP 1995-61898		19950224		

AB Adhesives for bonding laminates with improved peeling strength and surface appearance contain compds. including 1-4 oxetane rings and photocationic polymerization initiators. Thus, 100 parts p-ROCH2C6H4CH2OR (R = 2-oxetanylbutyl) and 4 parts p-(Ph2S)SC6H4SPh+ SbF6- were mixed, applied on a biaxially drawn polypropylene (I) film, laminated with an undrawn I film (untreated on the surface), and irradiated with UV to give a test piece showing peeling strength ≥500 g/10 mm and good heat creep resistance.

- L3 ANSWER 25 OF 28 CAPLUS COPYRIGHT 2007 ACS on STN
- AN 1996:660747 CAPLUS
- DN 125:279010
- TI Active energy-curable oxetane compositions for paper coatings with good gloss, adhesion, wear resistance, and flexibility
- IN Niwa, Makoto; Oota, Hiroyuki
- PA Toa Gosei Kk, Japan
- SO Jpn. Kokai Tokkyo Koho, 11 pp.
- CODEN: JKXXAF
- DT Patent
- LA Japanese
- FAN.CNT 1

LATA CIAI I				
PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI JP 08218296	Α	19960827	JP 1995-50415	19950215
JP 3364915	B2	20030108		
PRAI JP 1995-50415		19950215		
GT				

AB The compns. comprise compds. having 1-4 oxetane rings, cationic photopolymn. initiators, and optionally epoxides, vinyl ethers, and (meth) acryloyl group-containing compds. Thus, a composition comprising 100 parts a compound with 2 oxetane rings I and 4 parts an initiator II was applied to a paper and exposed to UV to give test pieces with JIS K 5400 cross-cut adhesion 8-10, no crack by bending test, >90% in 60° gloss, and steel wool abrasion resistance.

- L3 ANSWER 26 OF 28 CAPLUS COPYRIGHT 2007 ACS on STN
- AN 1973:97399 CAPLUS
- DN 78:97399

- TI Reductive cleavage of polycyclic oxetanes
- AU Sauers, Ronald R.; Schinski, William; Mason, Marion M.; O'Hara, Elizabeth; Byrne, Bryan
- CS Sch. Chem., Rutgers State Univ., New Brunswick, NJ, USA
- SO Journal of Organic Chemistry (1973), 38(4), 642-6 CODEN: JOCEAH; ISSN: 0022-3263
- DT Journal
- LA English
- GI For diagram(s), see printed CA Issue.
- AB The action of H and catalysts, Li-ethylenediamine, Li-NH3, and alane on several polycyclic oxetanes (I, R = H, Ph, CH2Ph, α -naphthyl) is reported. In general, ring cleavages were effected which produced several novel alcs.
- L3 ANSWER 27 OF 28 CAPLUS COPYRIGHT 2007 ACS on STN
- AN 1969:414144 CAPLUS
- DN 71:14144
- TI Oxetane copolymers
- IN Maloney, Daniel E.
- PA du Pont de Nemours, E. I., and Co.
- SO U.S., 4 pp. CODEN: USXXAM
- DT Patent
- LA English
- FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
ΡI	US 3440231	Α	19690422	US 1967-610250	19670119
	FR 1551586	Α	19681227	FR 1968-1551586	19680117
	NL 6800879	Α	19680722	NL 1968-879	19680119
	GB 1154535	Α	19690611	GB 1968-1154535	19680119
PRAI	US 1967-610250	Α	19670119		

AB Acyl halide- α -olefin copolymers were treated with 3-amino- (I) or 3-hydroxyoxetane to give copolymers which were useful as coatings for decreasing the shrinking tendencies of proteinaceous and cellulosic substrates. Thus, 10 g. of a random ethylene (II)-methacryloyl chloride copolymer was prepared by reacting a chlorinating agent such as PCl5 with an II-methacrylic acid copolymer, which was obtained by the process of Canadian Patent 655,298, and was dissolved in 450 ml. PhMe at 70°. Et3N (3.0 ml.) and 3.0 g. I were added to the solution and, after 30 min. at 70°, the copolymer (III) was precipitated by adding excess Me2CO. A 2% III solution in perchloroethylene was padded onto 8-in. sqs. of cotton poplin, impregnated with 0.01-0.09 weight % Zn(BF4)2. The poplin was heated 30 min. at 125°, then refluxed in PhMe. The amount of III on the fabric was reduced from 2.02 weight % to 0.88 weight %, after refluxing 4 hrs., and to 0.82 weight %, after refluxing 8 hrs. An II-Et acrylateacryloyl chloride terpolymer was reacted similarly with I. The modified copolymer exhibited higher abrasion resistances than the unmodified copolymers and can be molded into weather-resistant films.

- L3 ANSWER 28 OF 28 CAPLUS COPYRIGHT 2007 ACS on STN
- AN 1965:480121 CAPLUS
- DN 63:80121
- OREF 63:14690h,14691a-b
- TI Bis(trifluoromethyl)ketene
- AU England, D. C.; Krespan, C. G.
- CS E. I. du Pont de Nemours & Co., Wilmington, DE
- SO Journal of the American Chemical Society (1965), 87(17), 4019-20 CODEN: JACSAT; ISSN: 0002-7863

- DT Journal
- LA English
- OS CASREACT 63:80121
- GI For diagram(s), see printed CA Issue.
- AB Heating a mixture of (CF3)2CHCO2H and excess P2O5 up to 250° pot temps. gives over 90% (CF3)2C:C:O (I). I, b. 5°, and CF2:C(CF3)COF, b. 52°, are in equilibrium in the vapor phase over anionic catalysts such as NaF. Cycloaddn. to both the C:C and C:O groups of I can occur. Thus, I reacts with CH2:CHOBz at 100° to give 34% II and 42% III. Simple alkenes also add to I to form cyclobutanones and linear adducts. A condensed phase is necessary, so lower alkenes require higher pressures. A mixture obtained from I and C3H6 at 150° and 800 atmospheric, was separated

gas chromatography into .apprx.70% cyclobutanone derivative and 30% (CF3)2CHCOCH2CH:CH2. I reacts with trioxane in Et2O at 150° in the presence of ZnCl2 as catalyst to give IV, and with PhC.tplbond.CH at 100° to give V. Ir data were given.

=> d his

(FILE 'HOME' ENTERED AT 10:21:10 ON 27 APR 2007)

FILE 'CAPLUS' ENTERED AT 10:21:28 ON 27 APR 2007

L1 4682 S OXETANE

L2 11113 S ACRYLOYL

L3 28 S L1 AND L2

=> s l1 and carbamate

31159 CARBAMATE

L4 26 L1 AND CARBAMATE

=> s l4 and isocyanate

66562 ISOCYANATE

L5 4 L4 AND ISOCYANATE

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L5
     ANSWER 1 OF 4 CAPLUS COPYRIGHT 2007 ACS on STN
AN
     2006:54836 CAPLUS
DN
     144:128998
     Preparation of morpholinopyrimidines and related compounds as modulators
ΤI
     of interleukin-12 (IL-12) production.
IN
     Sun, Lijun; Demko, Zachary; Wada, Yumiko
PA
     Synta Pharmaceuticals Corp., USA
so
     PCT Int. Appl., 81 pp.
     CODEN: PIXXD2
DT
     Patent
LA
     English
FAN.CNT 2
     PATENT NO.
                         KIND
                                DATE
                                            APPLICATION NO.
                                                                    DATE
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PΙ
     WO 2006007532
                          A2
                                20060119
                                            WO 2005-US23346
                                                                    20050701
     WO 2006007532
                          A3
                                20060817
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             CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, EG, ES, FI, GB, GD,
             GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KM, KP, KR, KZ,
             LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NA,
             NG, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK,
             SL, SM, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU,
             ZA, ZM, ZW
         RW: AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE,
             IS, IT, LT, LU, LV, MC, NL, PL, PT, RO, SE, SI, SK, TR, BF, BJ,
             CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG, BW, GH,
             GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW, AM, AZ, BY,
             KG, KZ, MD, RU, TJ, TM
     AU 2005262322
                                            AU 2005-262322
                                20060119
                          Α1
     CA 2571178
                          Α1
                                20060119
                                            CA 2005-2571178
                                                                    20050701
     US 2006063739
                          A1
                                20060323
                                            US 2005-174173
                                                                    20050701
     EP 1765325
                          A2
                                20070328
                                            EP 2005-767834
                                                                    20050701
             AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE,
             IS, IT, LI, LT, LU, MC, NL, PL, PT, RO, SE, SI, SK, TR
PRAI US 2004-585124P
                          P
                                20040701
     WO 2005-US23346
                          W
                                20050701
     MARPAT 144:128998
os
GI
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AB Title compds. [I; R1 = N:CRaRb, NRc(CH2)nRc, cycloalkyl, aryl, heteroaryl; R2, R4 = Rc, halo, NO2, cyano, isothionitro, SRc, ORc; R2R4 = CO; R3 = Rc, alkenyl, alkynyl, ORc, O2CRc, SO2Rc, SORc, SRc, CORc, CO2Rc, etc.; R5 = H, alkyl; G = hydrazide, hydrazone, hydrazine, hydroxylamine, oxime, carbamate, thiocarbamate, guanidine, cyanoguanidine, urea, sulfamide, phosphoryl, Si(OH)2, CONRcCO, etc.; Y = bond, CH2, CO, C:NRc,

O, S, SO, SO2, NRc, etc.; U, V = N, CRc; W = O, S, SO, SO2, NRc, NCORc; Ra, Rb = H, alkyl, aryl, heteroaryl; Rc = H, alkyl, aryl, heteroaryl, cyclyl, heterocyclyl, etc.; n = 0-6], were prepared Thus, 3-[4-[N'-(3-methylbenzylidene) hydrazino]-6-morpholin-4-ylpyrimidin-2-yl]propan-1-ol (preparation given) was stirred with m-trifluoromethylphenyl isocyanate in MeCN containing cat. 4-dimethylaminopyridine to give (3-trifluoromethylphenyl)carbamic acid <math>3-[4-[N'-(3-methylbenzylidene) hydrazino]-6-morpholin-4-ylpyrimidin-2-yl]propyl ester. The latter inhibited IL-12 production with an IC50 of <25 nM.

=> d 2-4 bib abs

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L5
    ANSWER 2 OF 4 CAPLUS COPYRIGHT 2007 ACS on STN
ΑN
     2004:964865 CAPLUS
DN
    141:395968
TI
    Oxetane compounds containing styrenic functionality
IN
    Musa, Osama M.
PA
    National Starch and Chemical Investment Holding Corporation, USA
SO
    U.S. Pat. Appl. Publ., 5 pp.
    CODEN: USXXCO
DT
    Patent
    English
LA
FAN.CNT 1
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		TENT I						DATE			APPL					D	ATE	
PI	US	2004	2250	71		A1		2004	1111							2	0030	506
		6953						2005										
	WO	2004																
		W:						AU,										
			CN,	CO,	CR,	CU,	CZ,	DE,	DK,	DM,	DZ,	EC,	EE,	EG,	ES,	FI,	GB,	GD,
			GE,	GH,	GM,	HR,	HU,	ID,	IL,	IN,	IS,	JP,	KΕ,	KG,	ΚP,	KR,	ΚZ,	LC,
			LK,	LR,	LS,	LT,	LU,	LV,	MA,	MD,	MG,	MK,	MN,	MW,	MX,	MZ,	NA,	NI,
			NO,	NZ,	OM,	PG,	PH,	PL,	PT,	RO,	RU,	SC,	SD,	SE,	SG,	SK,	SL,	SY,
			ТJ,	TM,	TN,	TR,	TT,	TZ,	UA,	ŪĠ,	US,	UΖ,	VĊ,	VN,	YU,	ZA,	ZM,	ZW
		RW:	BW,	GĤ,	GM,	KΕ,	LS,	MW,	MZ,	SD,	SL,	SZ,	TZ,	ŪĠ,	ZM,	ZW,	AM,	ΑZ,
			BY,	KG,	ΚZ,	MD,	RU,	TJ,	TM,	ΑT,	BE,	BG,	CH,	CY,	CZ,	DE,	DK,	EE,
			ES,	FI,	FR,	GB,	GR,	HU,	ΙE,	IT,	LU,	MC,	NL,	PL,	PT,	RO,	SE,	SI,
			SK,	TR,	BF,	ВJ,	CF,	CG,	CI,	CM,	GΑ,	GN,	GQ,	GW,	ML,	MR,	NE,	SN,
			TD,	TG														
	CN	1697	832			Α		2005	1116		CN 2	004-	8000	0440		2	0040	421
	EΡ	1620	417			A1		2006	0201		EP 2	004-	7608	29		2	0040	421
		R:	ΑT,	BE,	CH,	DE,	DK,	ES,	FR,	GB,	GR,	IT,	LI,	LU,	NL,	SE,	MC,	PT,
								TR,										
	JP	2006	5165	51		T		2006	0706		JP 2	005-	5182	01		2	0040	421
	CN	1944	418			Α		2007										
	US	2005	1924	46		A1		2005										
PRAI	US	2003	-430	086		Α		2003	0506					•				
		2004						2004										
	WO	2004	-US1	2489		W		2004	0421									

The invention relates to compds. containing an oxetane functionality AB and a styrenic functionality having structure I; wherein R1 is a Me or Et group; R2 and R3 are H or a Me or Et group; R4 is a direct bond or a divalent hydrocarbon; X and Y are independently a direct bond or an ether, ester, amide, or carbamate group, provided both X and Y are not a direct bond; Q is a divalent hydrocarbon (which may contain heteroatoms of N, O, or S); and G is -OR1, -SR1, or -N(R2)(R3), in which R1, R2 and R 3 are as described above.. The oxetane functionality is homopolymerizable in reactions that undergo cationic or anionic ring opening, and the styrenic is polymerizable with compds. such as electron acceptor compds. The dual functionality allows for dual cure processing. Thus, styrene carbamate Et oxetane was prepared from 3-ethyl-3-hydroxymethyl-oxetane and 3-isopropenyl- α, α -dimethyl-benzyl isocyanate (m-TMI).

RE.CNT 70 THERE ARE 70 CITED REFERENCES AVAILABLE FOR THIS RECORD ALL CITATIONS AVAILABLE IN THE RE FORMAT

L5 ANSWER 3 OF 4 CAPLUS COPYRIGHT 2007 ACS on STN

AN 1996:22563 CAPLUS

DN 124:202752

TI Heterocyclic lipids with PAF antagonist activities 4. Synthesis of 3,3-bis(hydroxymethyl)-oxetane, -thietane and -azetidine, and 1,1-bis(hydroxymethyl)cycloalkane derivatives

AU Chung, Sung-Kee; Ban, Su Ho; Kim, Byung Eog; Woo, Soon Hyung

CS Dept. of Chemistry, Pohang Univ. of Science and Technology, Pohang, 790-784, S. Korea

SO Korean Journal of Medicinal Chemistry (1995), 5(2), 94-111 CODEN: KJMCE7; ISSN: 1225-0058

PB Korean Chemical Society

DT Journal

LA English

GI

AB Conformationally constrained analogs of platelet activating factor incorporating a lipophile and a pyridine-like heterocycle coupled to core groups such as 3,3-bis(hydroxymethyl)oxetanes I [X = 0, R1 =

CONH(CH2)17Me, (CH2)15Me, CONH(CH2)15Me, R2 = H, CONHCH2-2-pyridinyl], -thietanes I [X = S, R1 = CONH(CH2)17Me, R2 = H, CONHCH2-2-pyridinyl], -azetidines I [X = NAc, R1 = CONH(CH2)17Me, CONH(CH2)15Me, R2 = H, CONHCH2-2-pyridinyl], and 1,1-bis(hydroxymethyl)cycloalkanes I [X = (CH2)n, n = 1-4, R1 = CONH(CH2)17Me, CONH(CH2)15Me, R2 = H, CONHCH2-2-pyridinyl] through hydrogen bond accepting linkages such as ether, ester and carbamate have been synthesized as potent PAF receptor antagonists.

- L5 ANSWER 4 OF 4 CAPLUS COPYRIGHT 2007 ACS on STN
- AN 1996:22562 CAPLUS
- DN 124:202751
- TI Heterocyclic lipids with PAF antagonist activities 3. Synthesis of 2,4-bis(hydroxymethyl)-oxetane and 1,3-bis(hydroxymethyl)cyclobutane derivatives
- AU Chung, Sung-Kee; Ban, Su Ho; Woo, Soon Hyung
- CS Dep. of Chemistry, Pohang Univ. of Science and Technology, Pohang, 790-784, S. Korea
- SO Korean Journal of Medicinal Chemistry (1995), 5(2), 84-93 CODEN: KJMCE7; ISSN: 1225-0058
- PB Korean Chemical Society
- DT Journal
- LA English

GI

AB Conformationally constrained analogs of platelet activating factor incorporating a lipophile and a pyridine-like heterocycle linked to core groups such as 2,4-bis(hydroxymethyl)oxetane, e.g. I, and 1,3-bis(hydroxymethyl)cyclobutane, e.g. II, via hydrogen bond acceptors such as carbamate and ether have been synthesized as potent PAF receptor antagonists.

Inventor Information for 10/588072

Inventor Name	City	State/Country
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MORINAKA, KATSUTOSHI	KANAGAWA	JAPAN
UCHIDA, HIROSHI	KANAGAWA	JAPAN
Appininto Contents Retitioninto Atty/Arentinto Continuity/Reexem	Foreign@ata Inventors Address	Frees Prestinto PrestrantPub
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10/588,072

